

Herstellung eines CMOS-Inverters im Doppelwannen-Prozeß



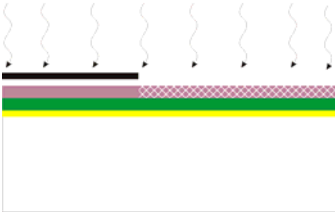
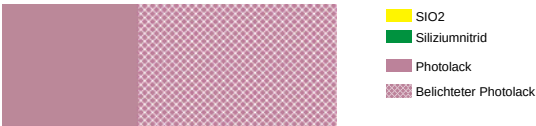
Siliziumnitrid abscheiden



Photolack abscheiden



Photolack belichten

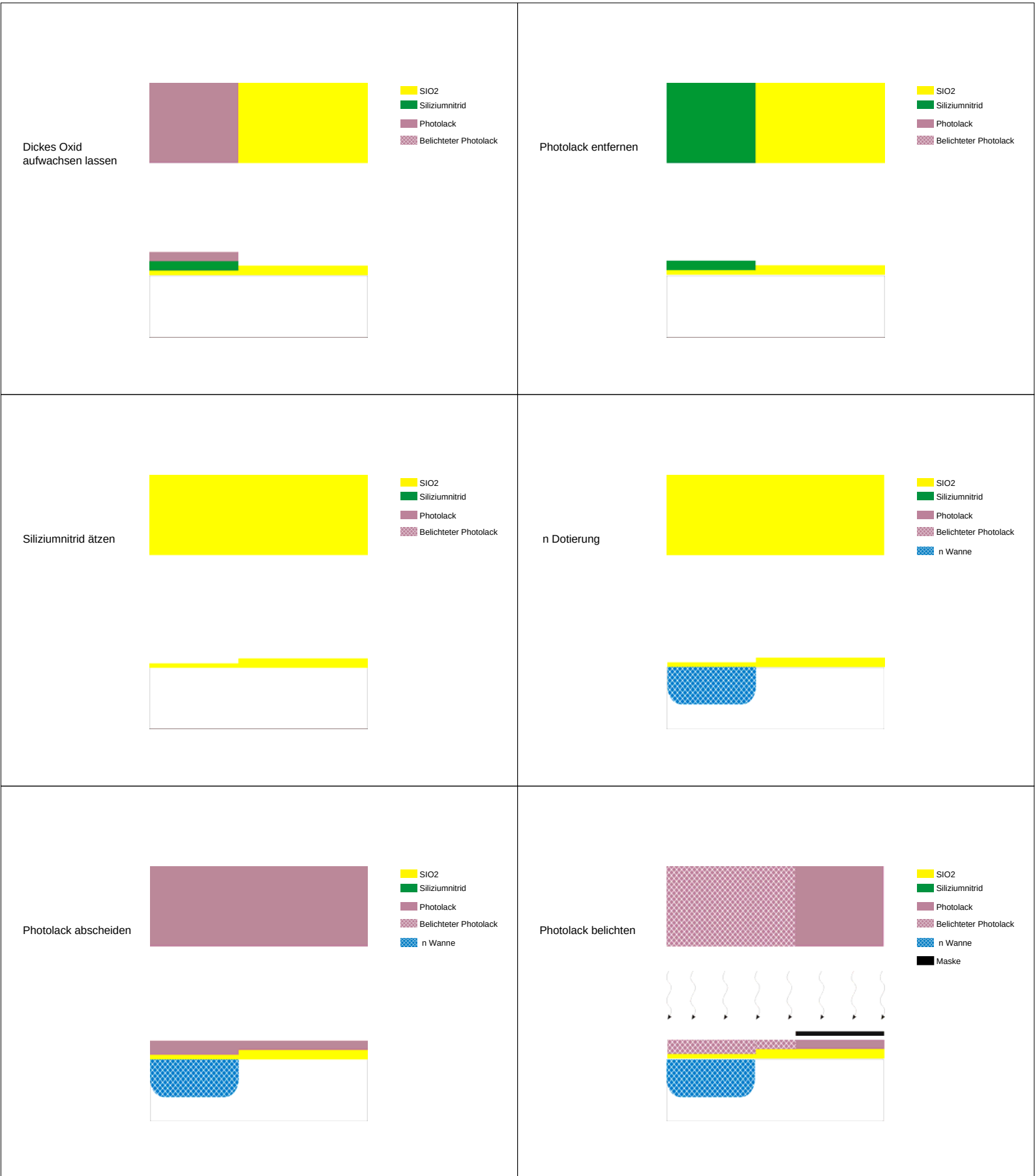


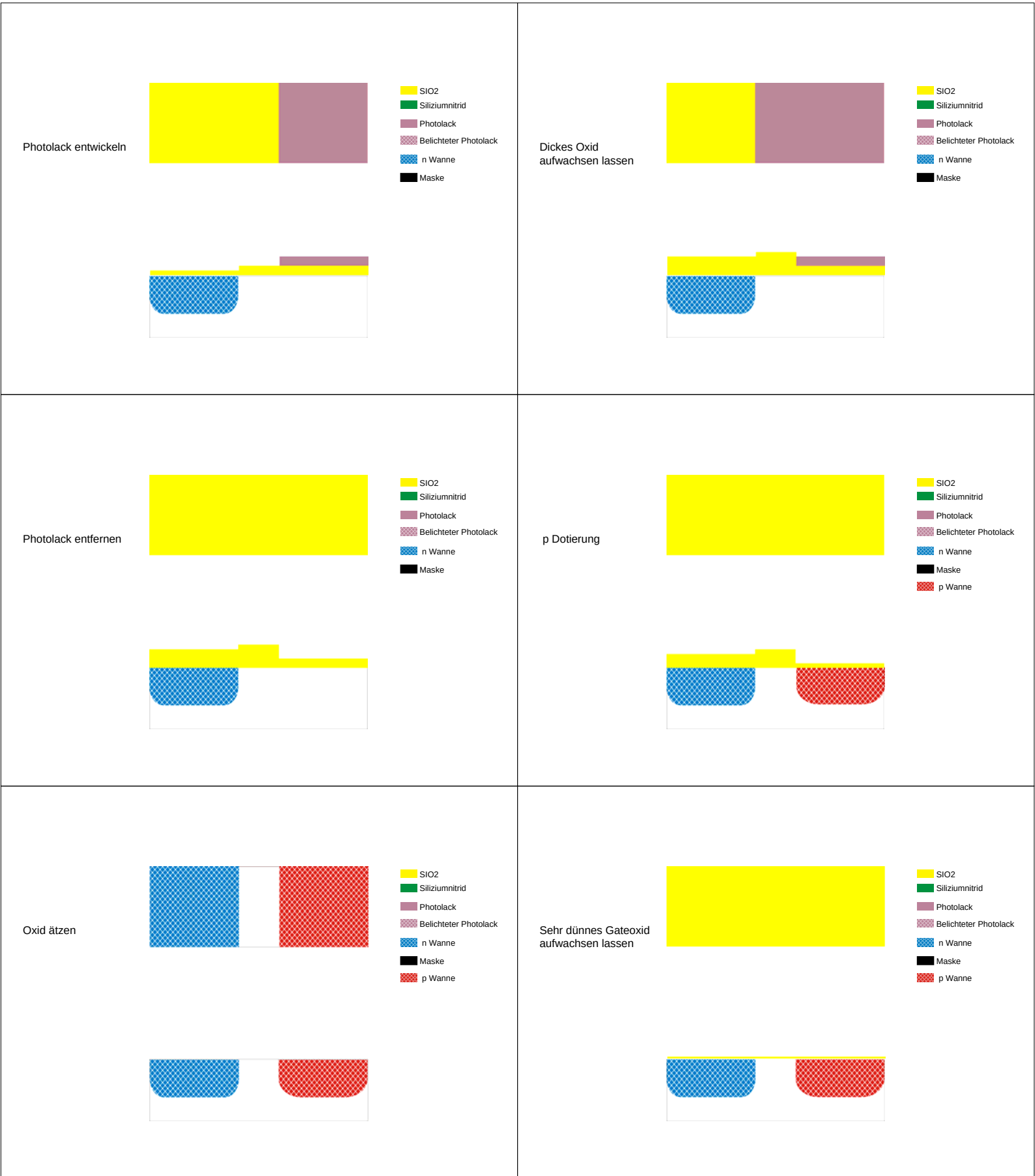
Photolack entwickeln



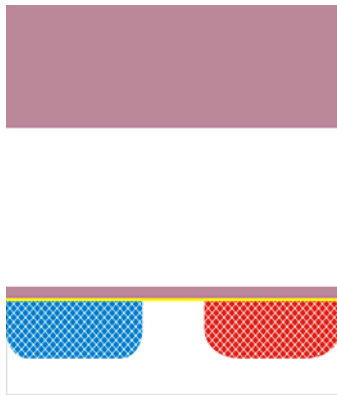
Siliziumnitrid ätzen





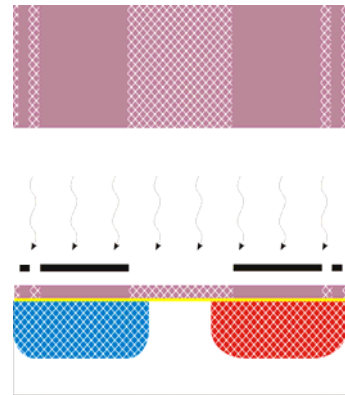


Photolack abscheiden



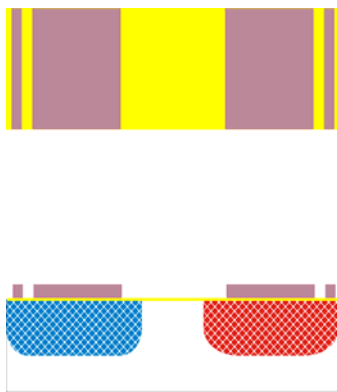
- SiO2
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne

Photolack belichten



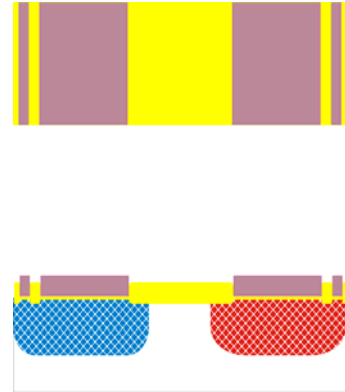
- SiO2
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne

Photolack entwickeln



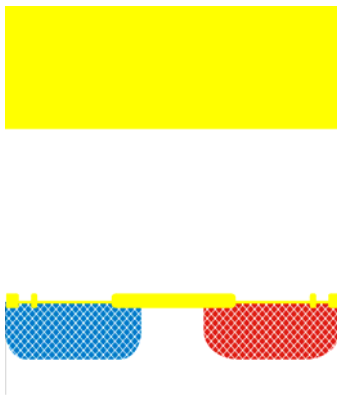
- SiO2
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne

Dickes Oxid aufwachsen lassen



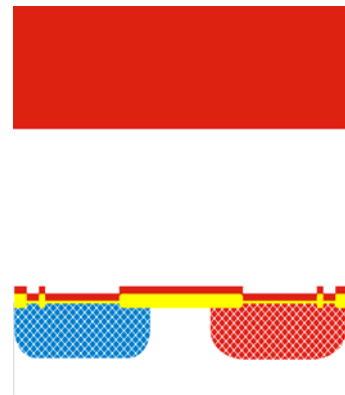
- SiO2
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne

Photolack entfernen

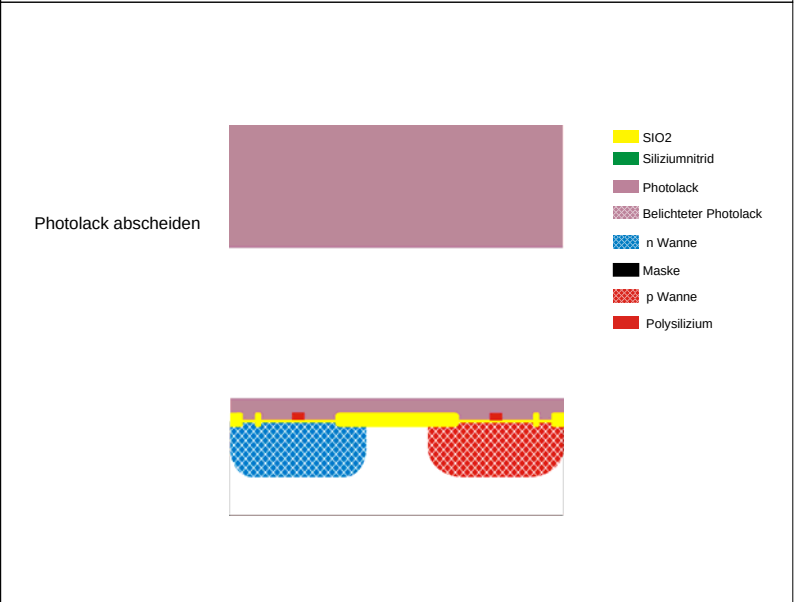
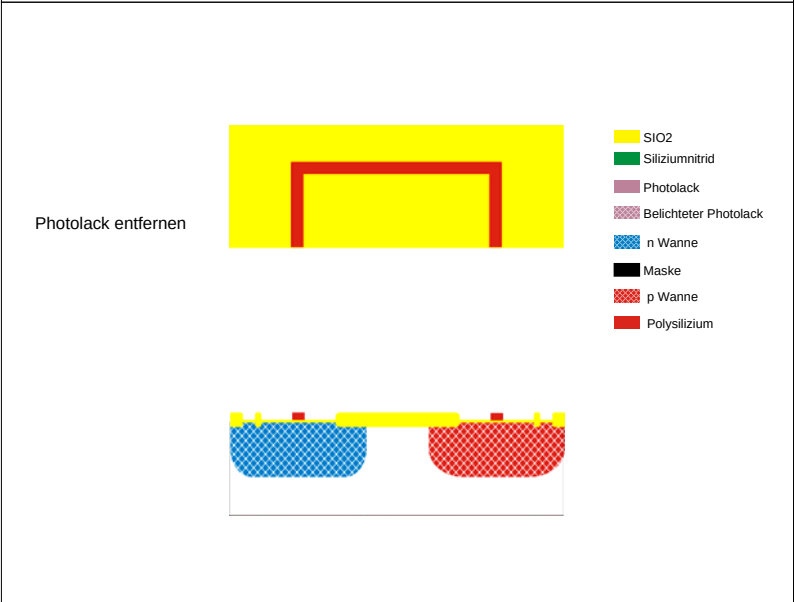
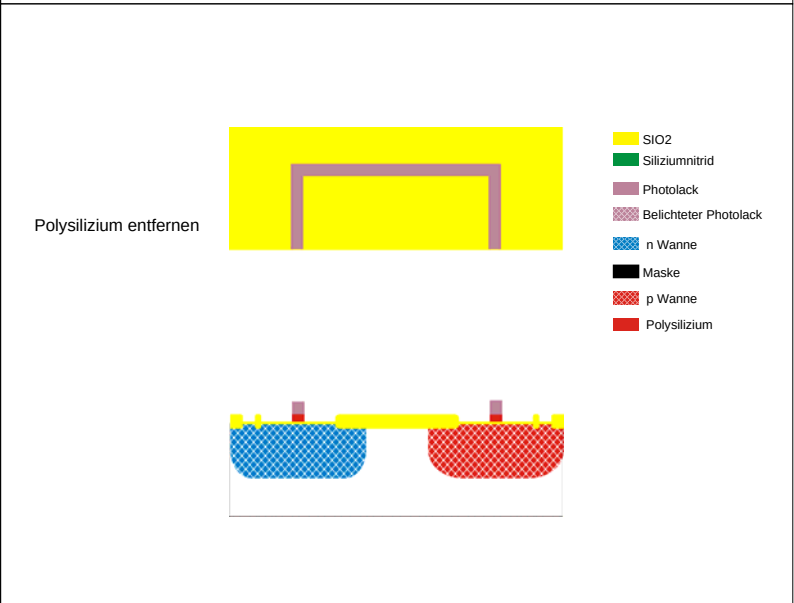
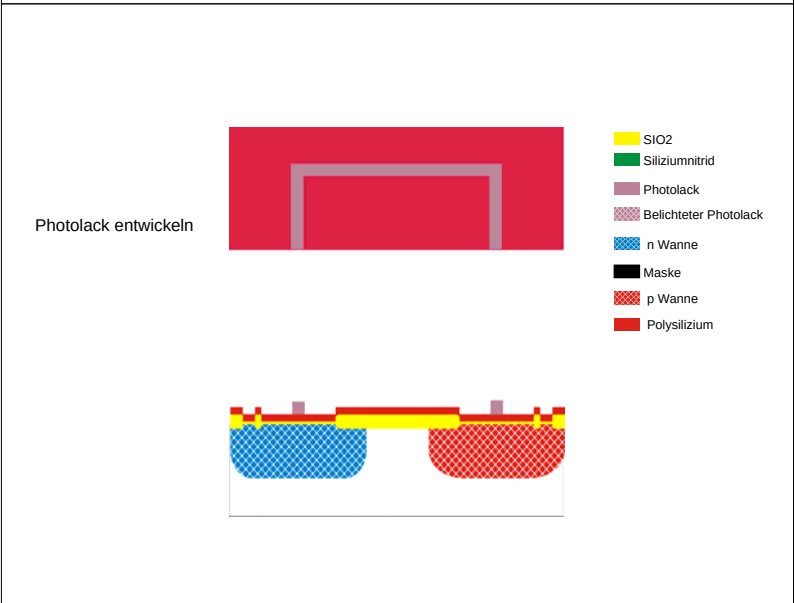
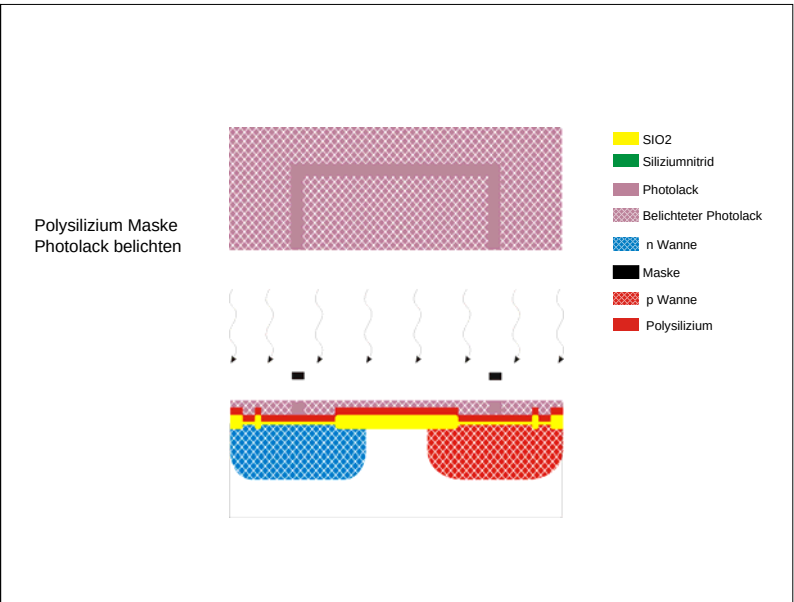
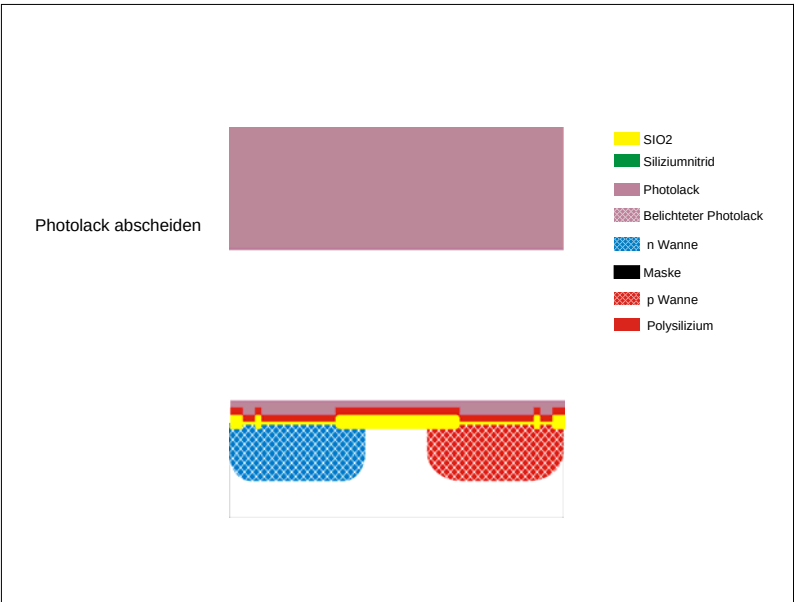


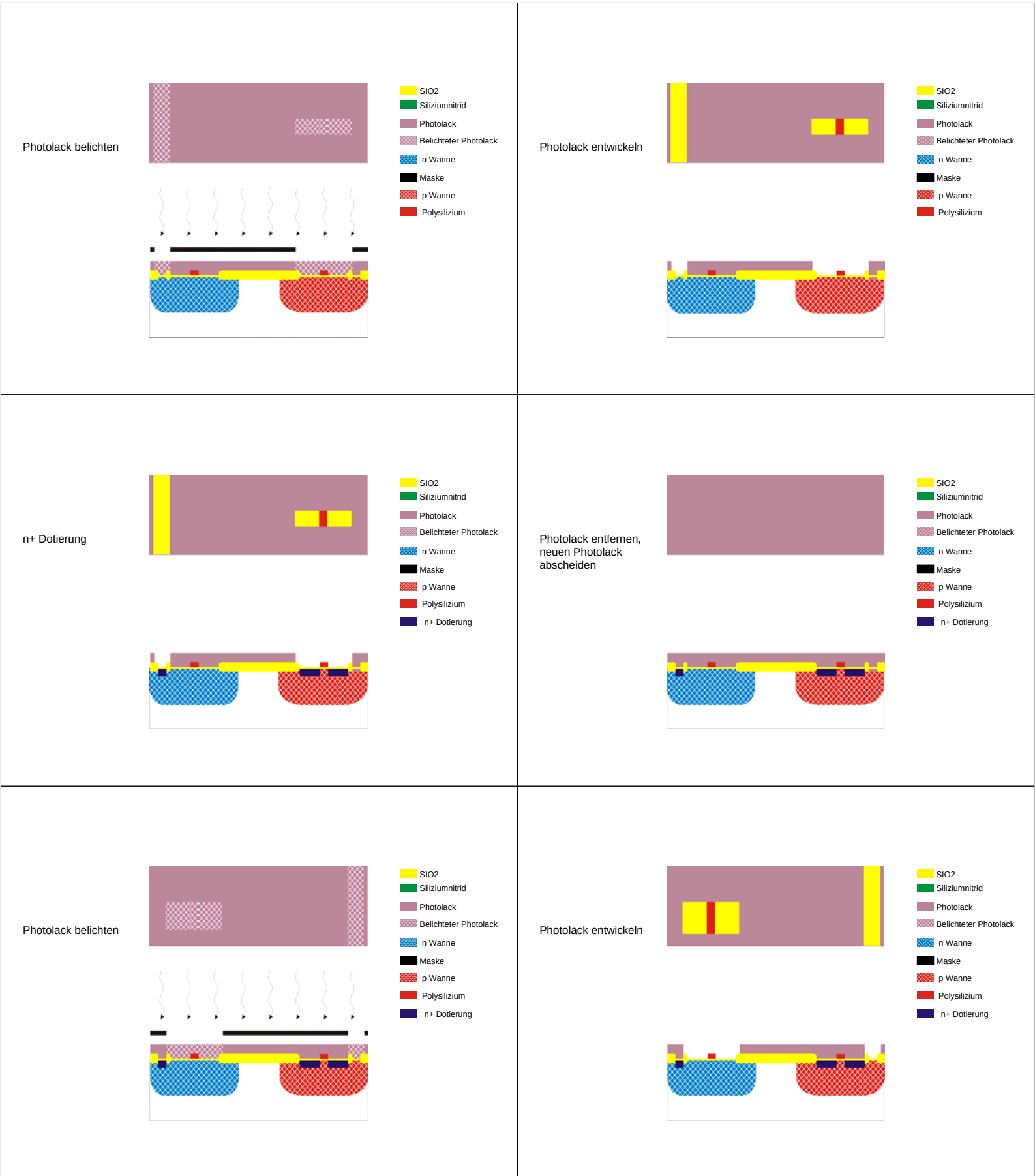
- SiO2
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne

Polysilizium Schicht

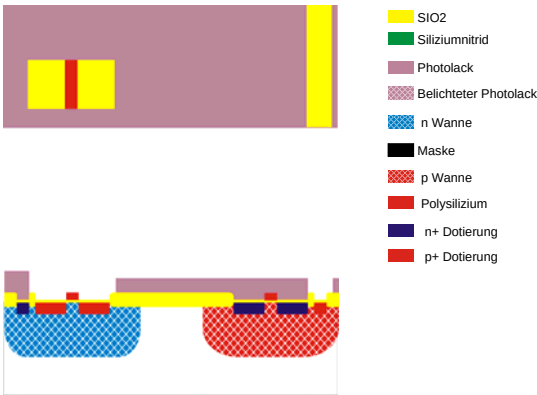


- SiO2
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne
- Polysilizium

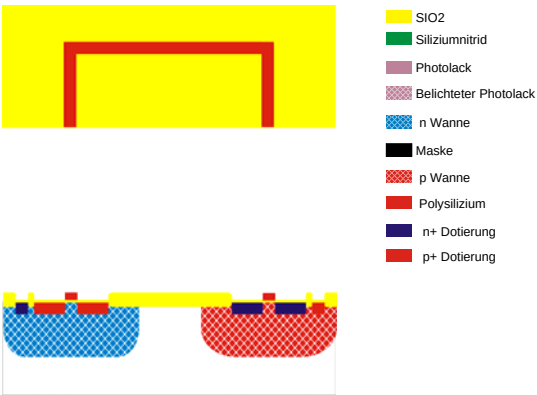




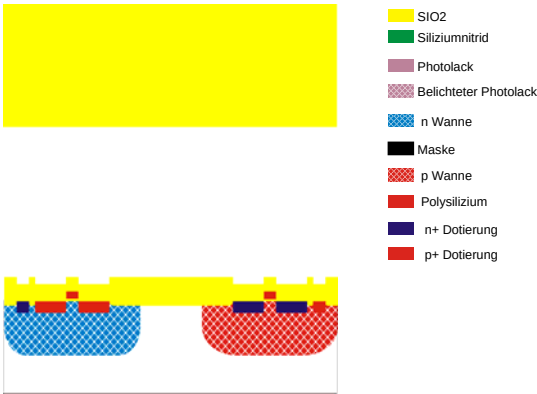
p+ Dotierung



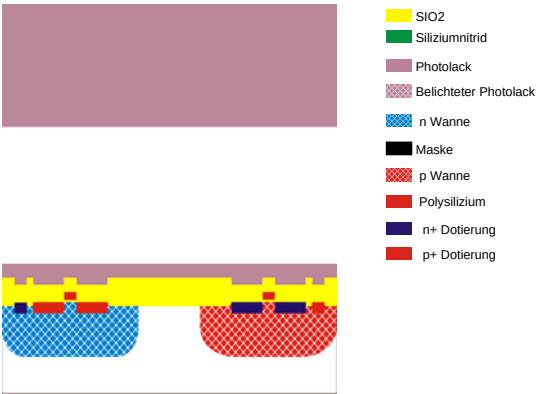
Photolack entfernen



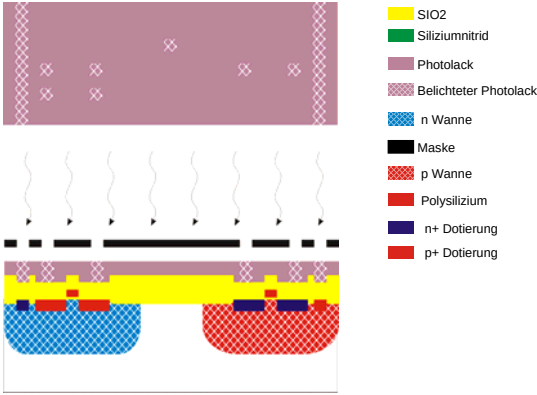
Dickes Oxid aufwachsen lassen



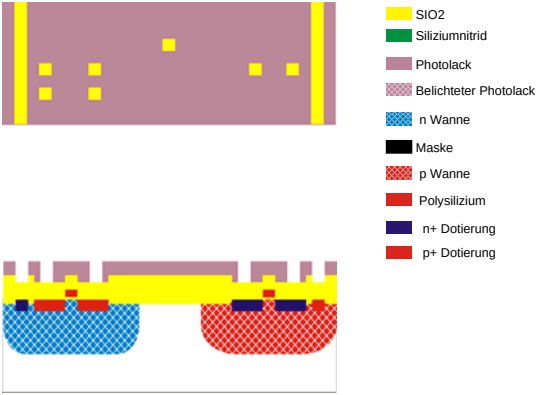
Photolack abscheiden



Photolack belichten mit Kontakt Maske



Photolack entwickeln



	SiO ₂
	Siliziumnitrid
	Photolack
	Belichteter Photolack
	n Wanne
	Maske
	p Wanne
	Polysilizium
	n+ Dotierung
	p+ Dotierung

	SiO ₂
	Siliziumnitrid
	Photolack
	Belichteter Photolack
	n Wanne
	Maske
	p Wanne
	Polysilizium
	n+ Dotierung
	p+ Dotierung

[illegible]

	SiO ₂
	Siliziumnitrid
	Photolack
	Belichteter Photolack
	n Wanne
	Maske
	p Wanne
	Polysilizium
	n+ Dotierung
	p+ Dotierung
	Aluminium

	SiO ₂
	Siliziumnitrid
	Photolack
	Belichteter Photolack
	n Wanne
	Maske
	p Wanne
	Polysilizium
	n+ Dotierung
	p+ Dotierung
	Aluminium



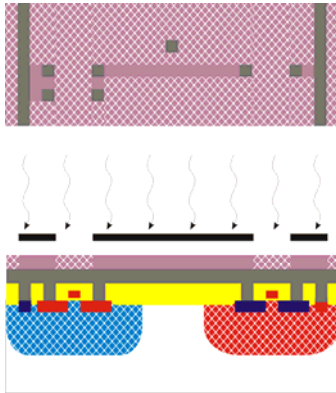
The diagram shows a cross-section of a device. At the top is a grey layer. Below it is a yellow layer. Under the yellow layer, there are two distinct regions: a blue one on the left and a red one on the right. Both regions have a cross-hatched pattern. Above each region, there are small rectangular structures, some of which are colored red and blue, possibly representing contacts or vias.

	SiO ₂
	Siliziumnitrid
	Photolack
	Belichteter Photolack
	n Wanne
	Maske
	p Wanne
	Polysilizium
	n+ Dotierung
	p+ Dotierung
	Aluminium

A diagram of a two-layer printed circuit board (PCB). The top layer is yellow, representing the copper surface. Below it are two prepreg layers: a blue one on the left and a red one on the right. Each prepreg layer contains copper traces and vias. The vias are shown as small red squares in the blue prepreg and small blue squares in the red prepreg, indicating through-hole connections between the layers.

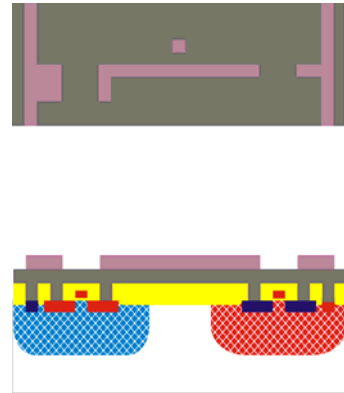
-  SiO₂
-  Siliziumnitrid
-  Photolack
-  Belichteter Photolack
-  n Wanne
-  Maske
-  p Wanne
-  Polysilizium
-  n+ Dotierung
-  p+ Dotierung
-  Aluminium

Photolack belichten



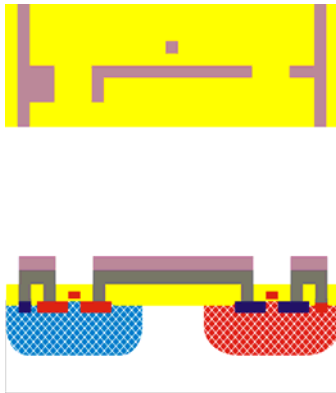
- SiO₂
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne
- Polysilizium
- n+ Dotierung
- p+ Dotierung
- Aluminium

Photolack entwickeln



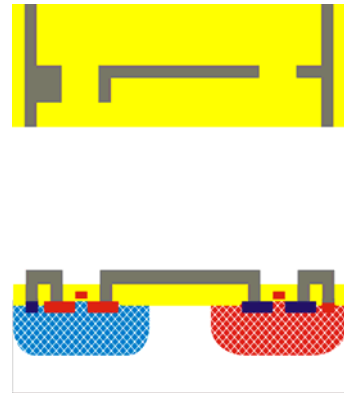
- SiO₂
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne
- Polysilizium
- n+ Dotierung
- p+ Dotierung
- Aluminium

Metall entfernen



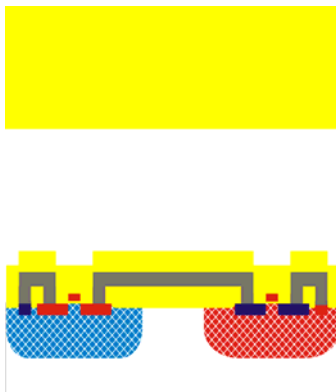
- SiO₂
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne
- Polysilizium
- n+ Dotierung
- p+ Dotierung
- Aluminium

Photolack entfernen



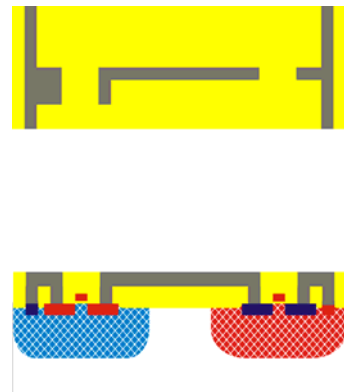
- SiO₂
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- Maske
- p Wanne
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- n+ Dotierung
- p+ Dotierung
- Aluminium

Dickes Oxid aufwachsen lassen

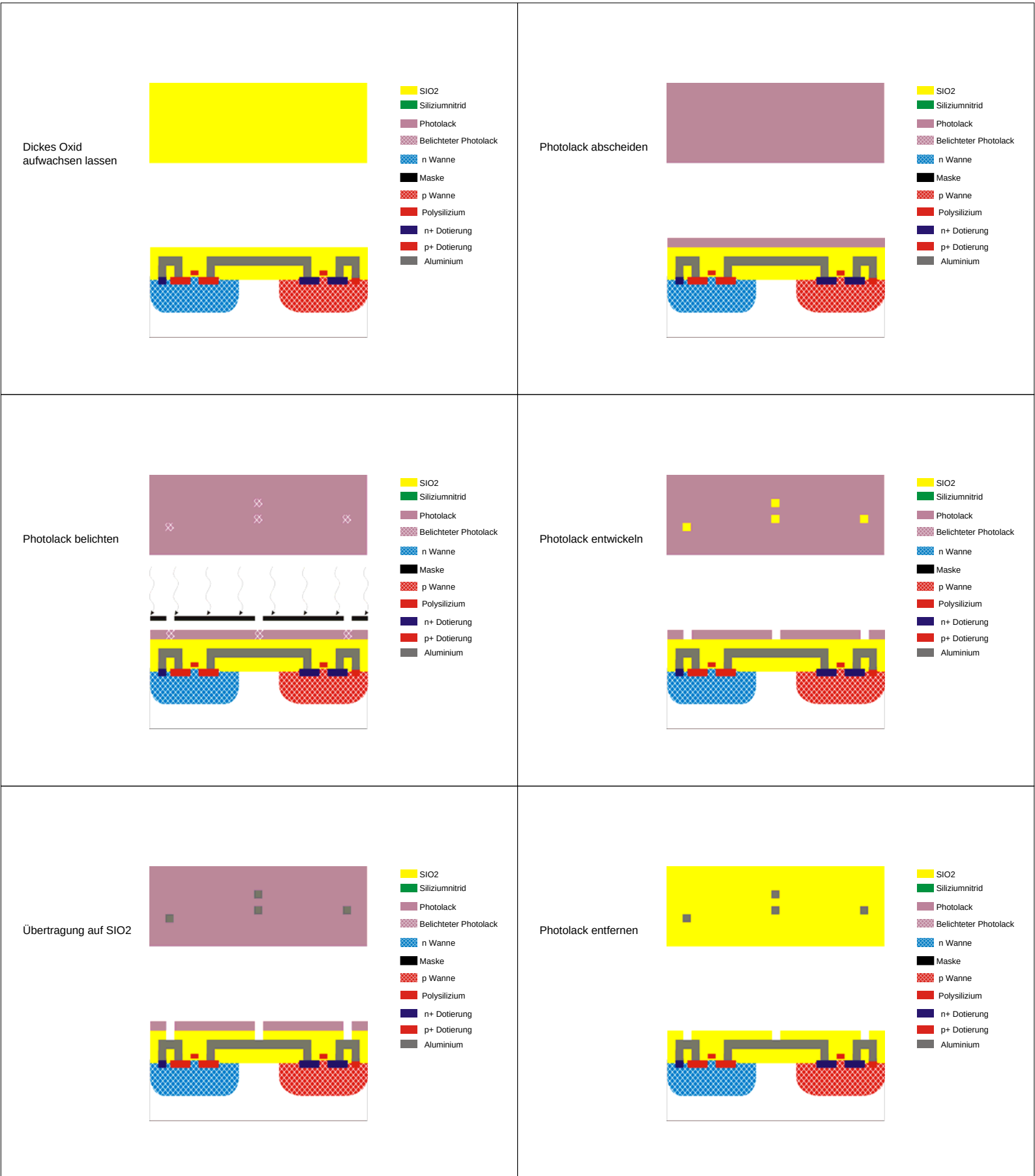


- SiO₂
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- n Wanne
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- p Wanne
- Polysilizium
- n+ Dotierung
- p+ Dotierung
- Aluminium

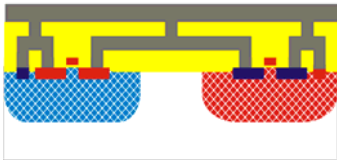
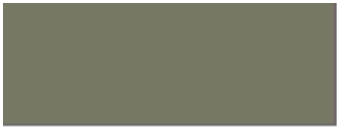
Oxid ätzen



- SiO₂
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne
- Polysilizium
- n+ Dotierung
- p+ Dotierung
- Aluminium

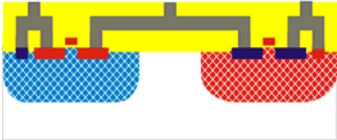


Metall Schicht



- SIO2
- Siliziumnitrid
- Photolack
- Belichteter Photolack
- n Wanne
- Maske
- p Wanne
- Polysilizium
- n+ Dotierung
- p+ Dotierung
- Aluminium

Metall entfernen



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